



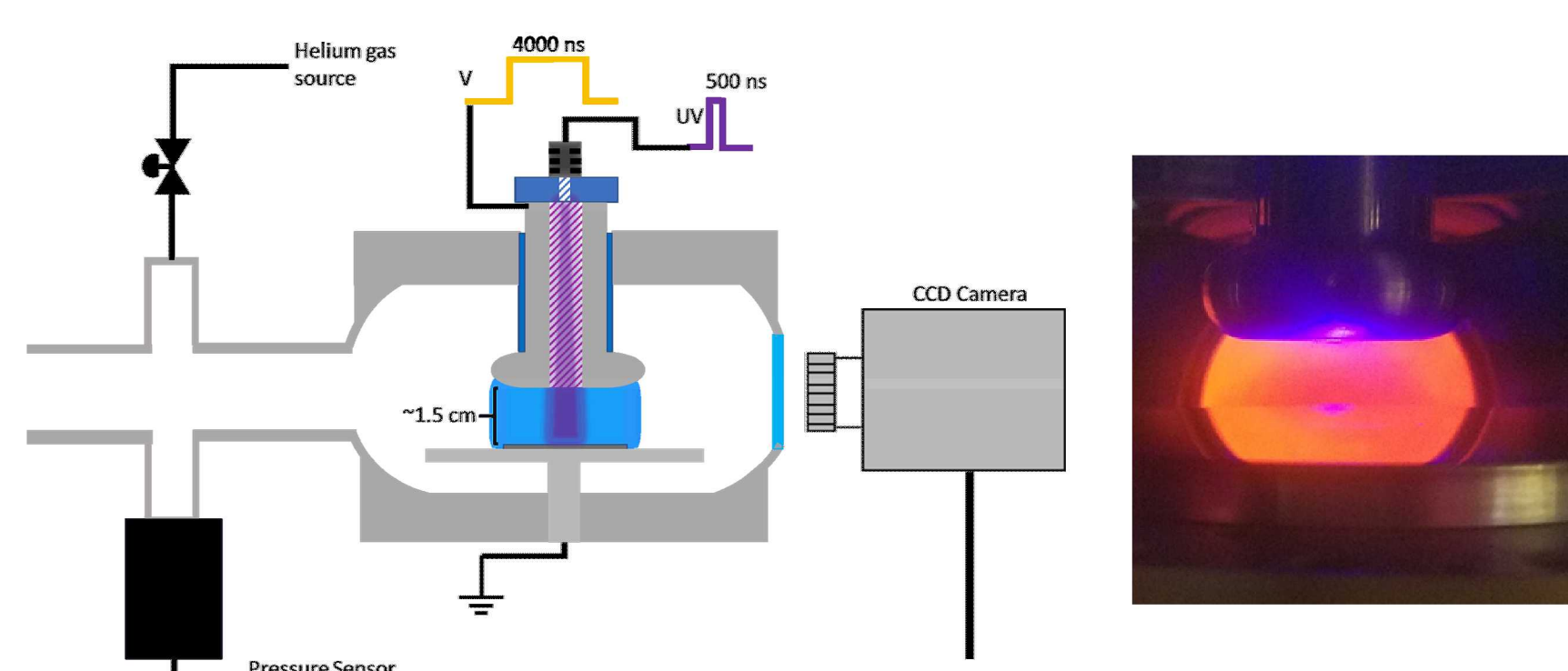
Characterization of photon-assisted plasma breakdown and development of *in-situ* surface spectroscopy in plane-to-plane discharges

Caroline Winters, George Nail, Michael Brumbach, and Ed Barnat

Gaining fundamental insight into plasma physics and breakdown phenomenon is critical in validating the predictive capabilities of Sandia's device performance codes. Of particular interest is surface-coupled breakdown processes induced by both cathode electron emission and ion/photon impingement. At $t=0$ s, a DC voltage pulse was applied to plane-to-plane electrodes for 4 μ s; concurrently, a UV diode produced 300 nm photons for 700 ns, initiating breakdown. Use of the diode forced a known breakdown solution, generating seed electrons from the cathode via photoionization of surface impurities, and removes the breakdown time stochasticity previously seen in DC pulse-only studies. The discharge has been run at 1, 5, and 10 Hz repetition rates to quantify a conditioning effect of the platinum cathode. This effect, potentially due to cathode surface chemistry has been observed and is the focus of current and future studies.

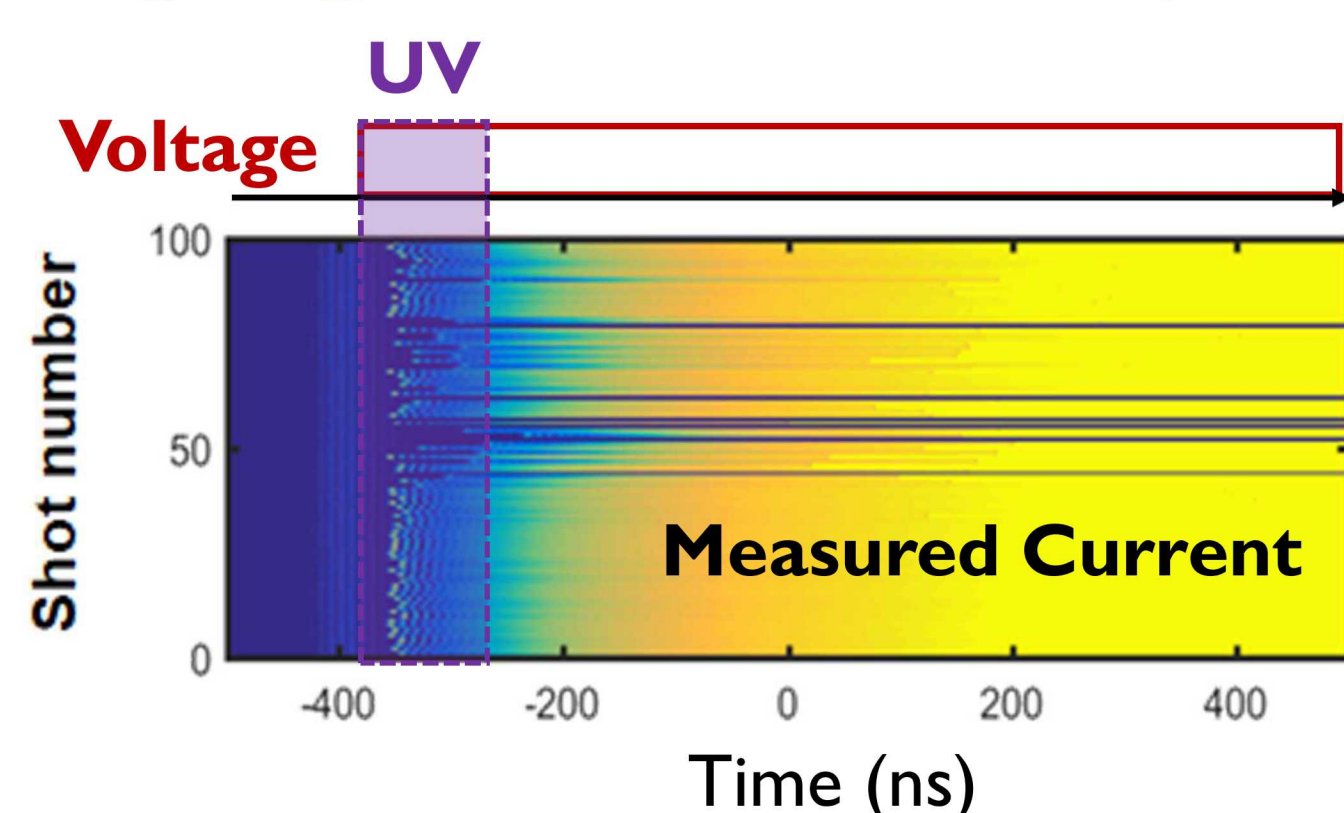
Experimental Set-up

Schematic and image of UV-illuminated plane-to-plane electrodes in helium



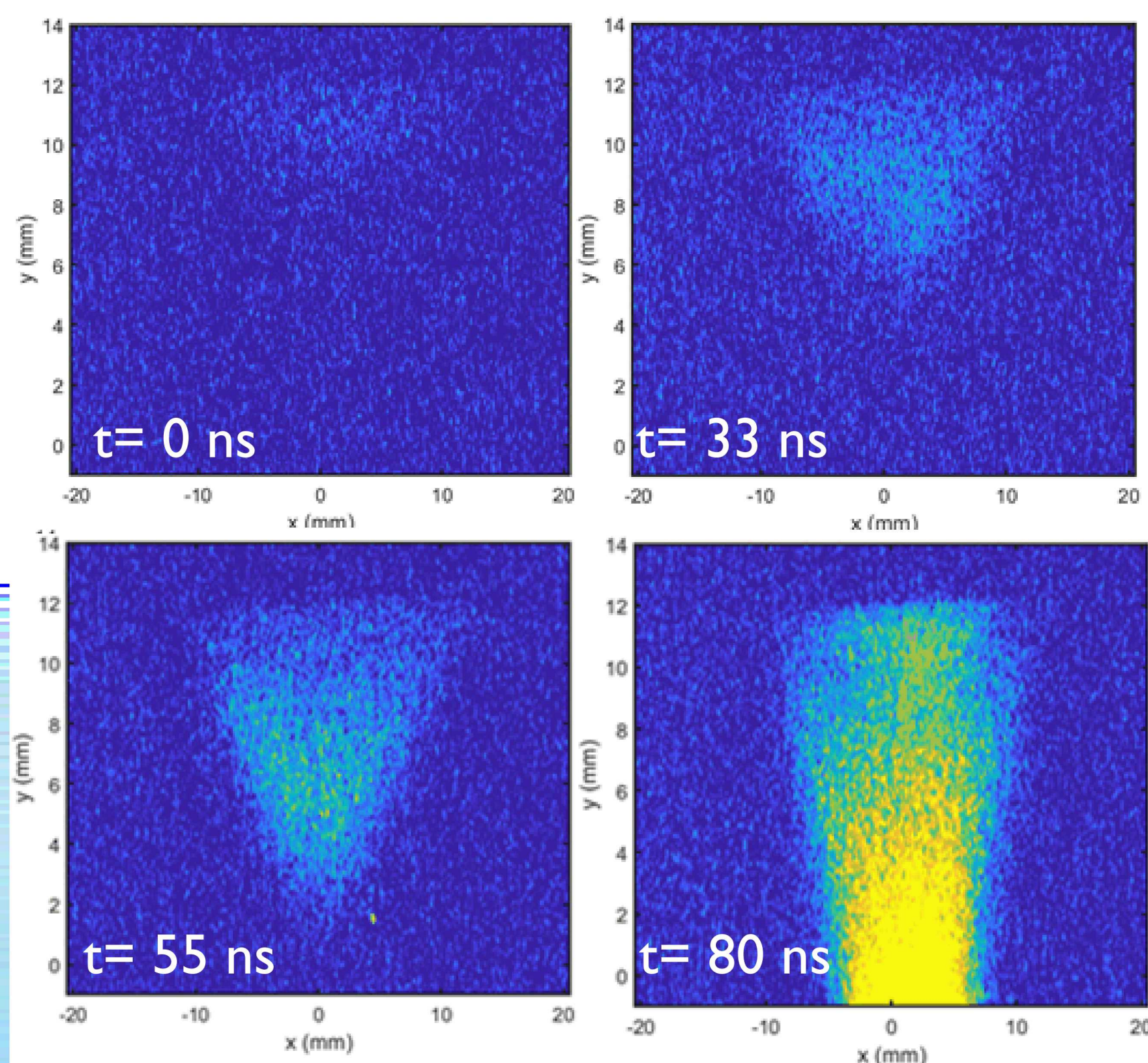
Anode: Stainless Steel
Cathode: 4" Pt wafer
Gas Pressure (p): 100 Torr
Gap (d): 1.5 cm
pd: 150 Torr cm
Paschen Breakdown: ~1.6 kV

Timing diagram for 100 shot sequence



Ionization wave

Single shot ICCD images of plasma

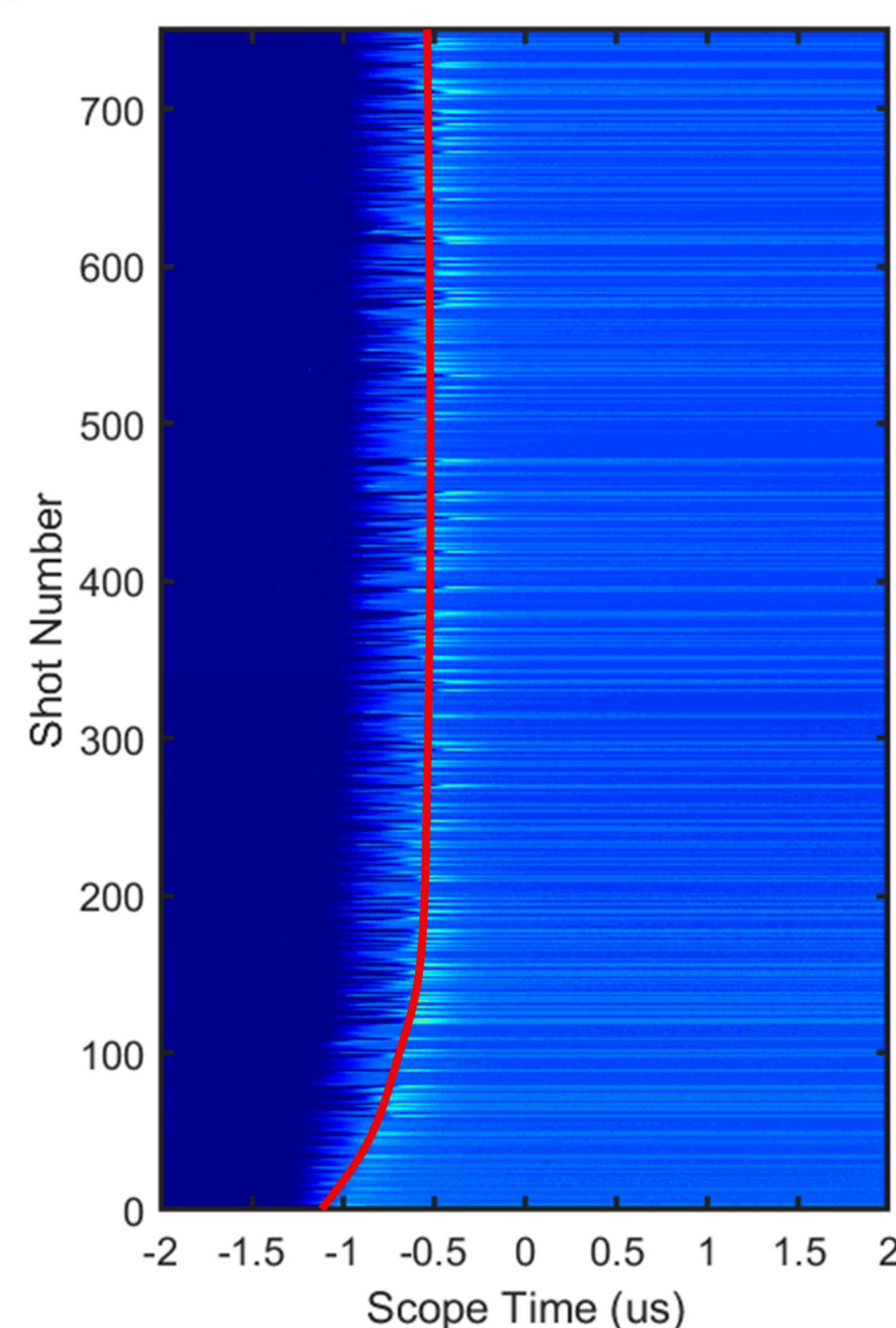


Helium, $P = 50$ Torr, $V = 2$ kV

- Propagation from anode to cathode shows diffuse breakdown wave front over the first 80 ns

Breakdown trends

Timing as a metric for surface conditioning



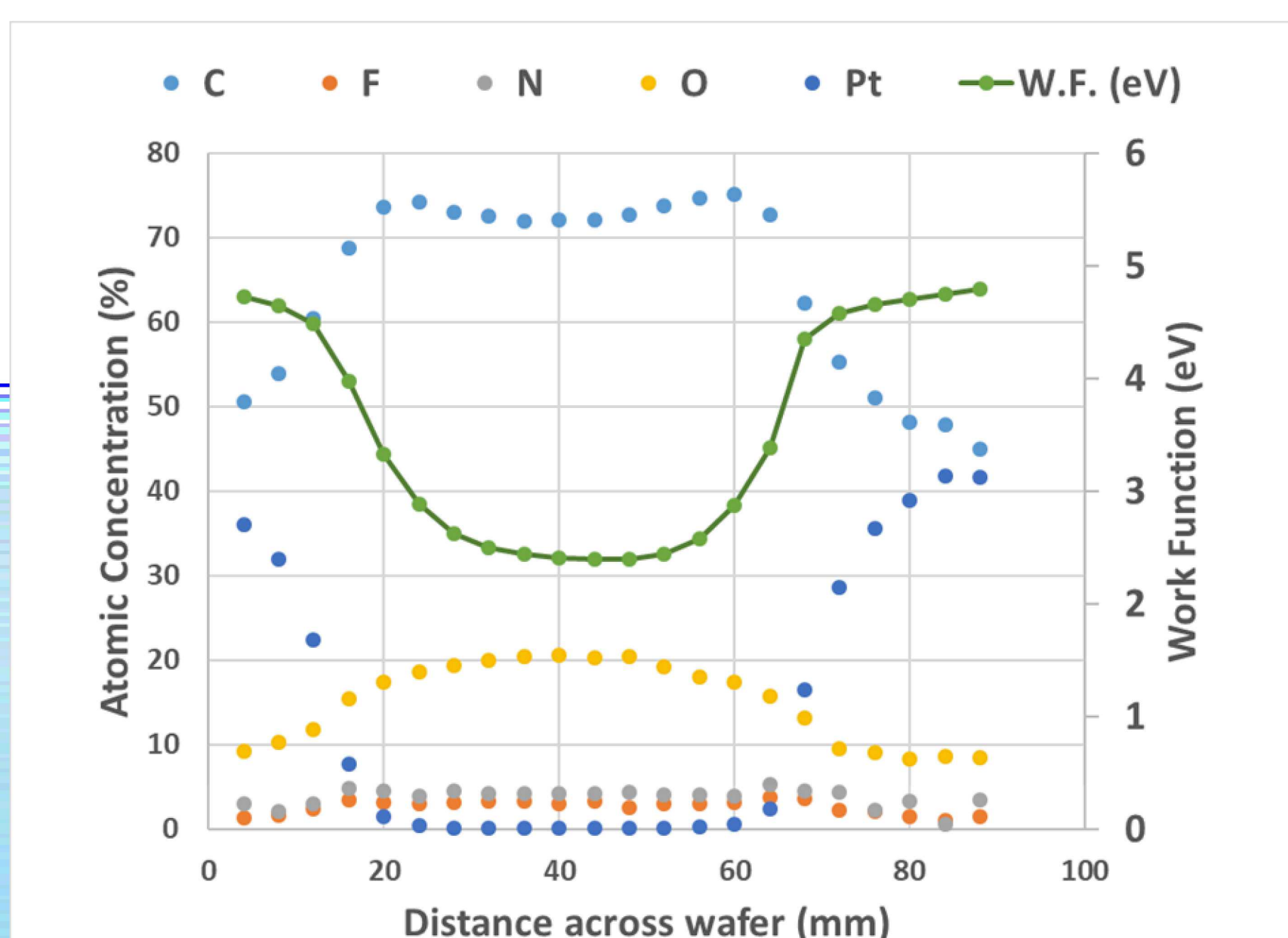
$P = 100$ Torr, $V = 1.5$ kV, 10 Hz rep. rate,
Data recorded at 1 Hz

- Breakdown time, τ , is defined as time for $I \geq 0.1$ A
- Measured $|\tau_s| = 1.3$ μ s after V_{app} , 600 ns after UV diode illumination ends
- Stability achieved after 504 shots \rightarrow 5040 breakdown events

X-ray Photoelectron Spectroscopy

Ex-situ focused x-ray beam measures spatially resolved surface species

Atomic concentration (%) across Pt wafer

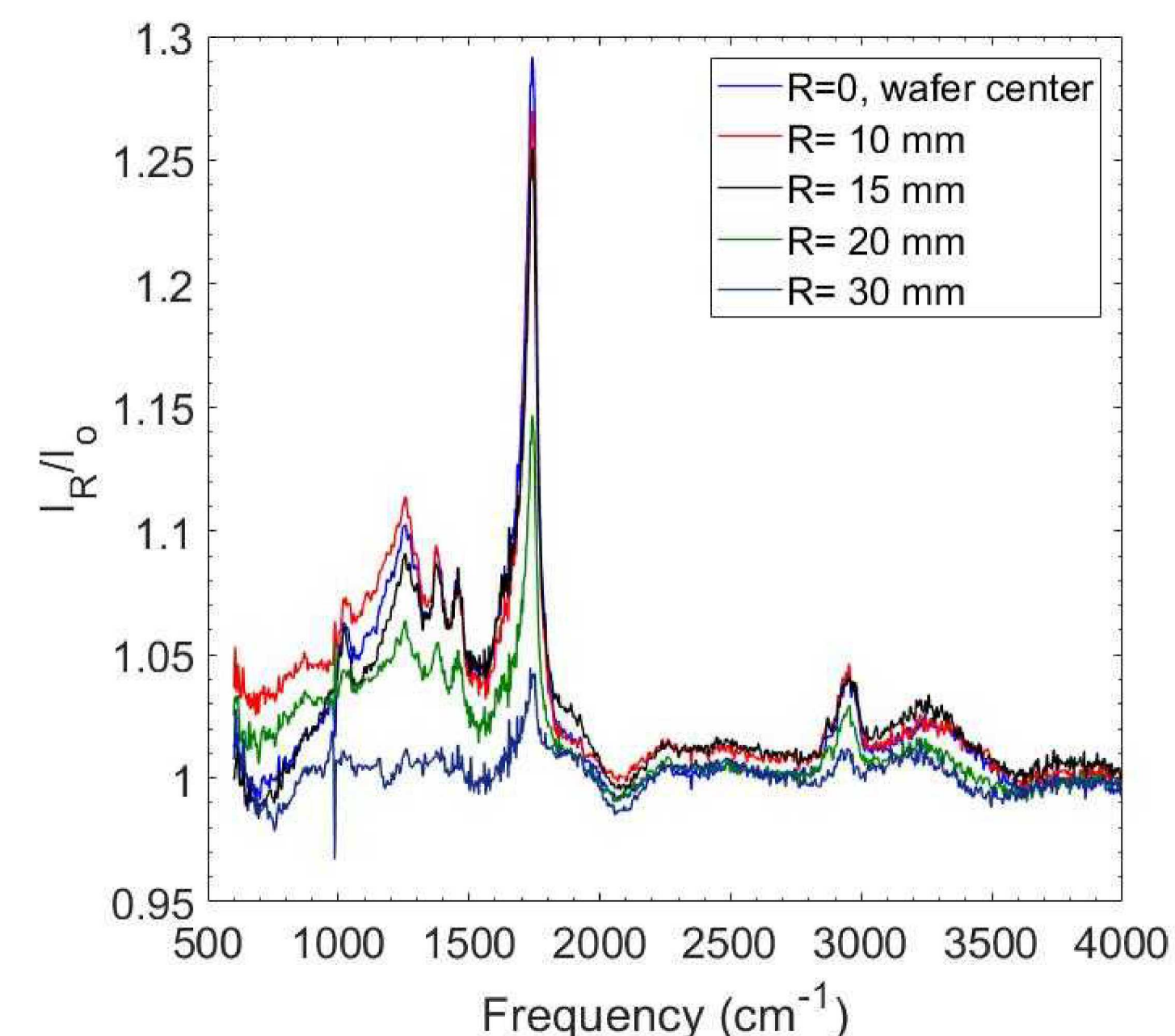


- Presence of platinum decreases while carbon and oxygen increase radially into region of plasma breakdown

Infrared Reflection Absorption Spectroscopy

- Both *ex-situ* and *in-situ* configurations
- Uses a commercially available FTIR
- Spectra averaged over 250 scans
- Sensitive to both gas and surface species

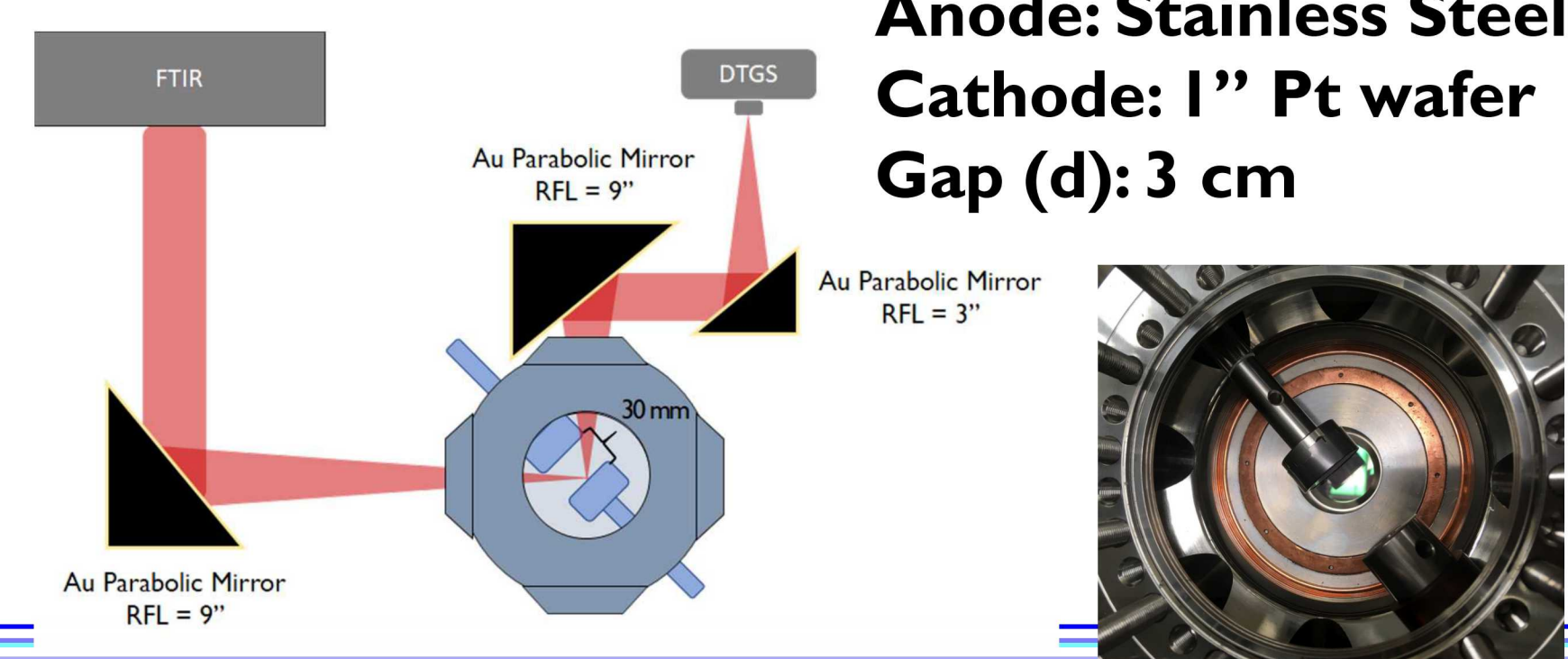
Ex-situ Spectra from Pt wafer



- Spectra have been normalized to an untreated wafer
- Intensity of C-bonds at 1700 cm^{-1} and 2900 cm^{-1} increase radially to wafer center
- IRRAS confirms XPS measured radial distribution of surface species

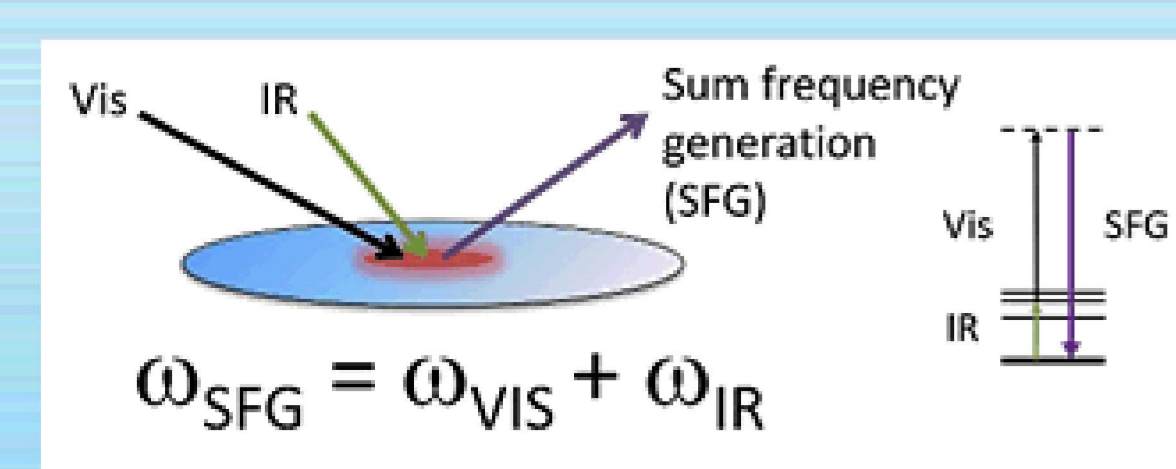
Future work: *in-situ* diagnostics

Schematic and images of IRRAS coupled to test cell



Anode: Stainless Steel
Cathode: 1" Pt wafer
Gap (d): 3 cm

Sum Frequency Generation (SFG)



- Current collaboration between S. Baldelli at the University of Houston and Sandia
- SFG further confirmed the presence of C-bonds on wafer